

Supplement to “Design of Gas Flow Field for a microchannel flow ALD Processing Chamber”

The continuity, momentum and energy equations of a steady-state compressible laminar flow field for the nitrogen gas are considered as follows.

$$\text{Continuity } \frac{\partial}{\partial x_j} (\rho U_j) = 0$$

$$\text{Momentum } \frac{\partial}{\partial x_j} (\rho U_j U_i) = -\frac{\partial P}{\partial x_i} + \frac{\partial \tau_{ij}}{\partial x_j} - \rho g \delta_{i3}, \quad \text{Stress tensor } \tau_{ij} = \mu \left(\frac{\partial U_i}{\partial x_j} + \frac{\partial U_j}{\partial x_i} - \frac{2}{3} \frac{\partial U_k}{\partial x_k} \delta_{ij} \right)$$

$$\text{Energy } \frac{\partial}{\partial x_j} [\rho U_j E] = -\frac{\partial (P U_i)}{\partial x_i} + \frac{\partial (\tau_{ij} U_i)}{\partial x_j} + \frac{\partial}{\partial x_j} \left(k \frac{\partial T}{\partial x_j} \right) - \rho g U_i \delta_{i3}, \quad E = h - \frac{P}{\rho} + \frac{1}{2} U_i U_i$$

where ρ , U , P , T , μ , h and δ are the density, velocity, pressure, temperature, molecular viscosity, enthalpy of the gas and the Kronecker delta, respectively, and the subscripts $i, j=1, 2$ and 3 are the tensor components.

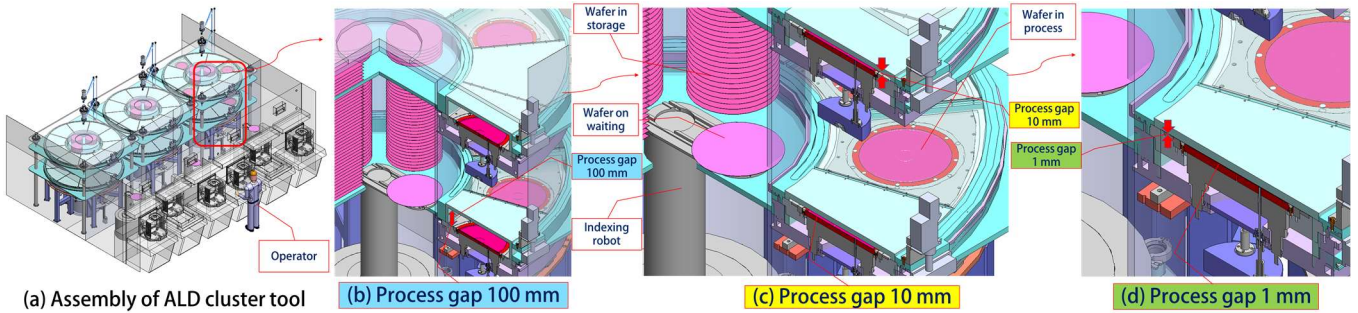
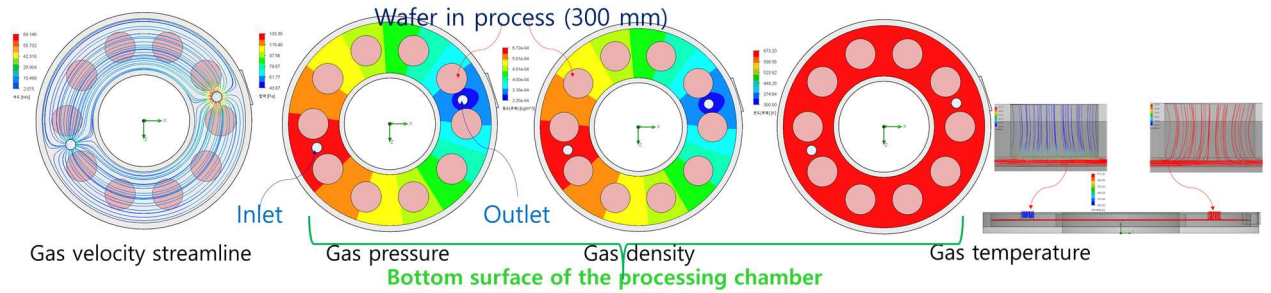
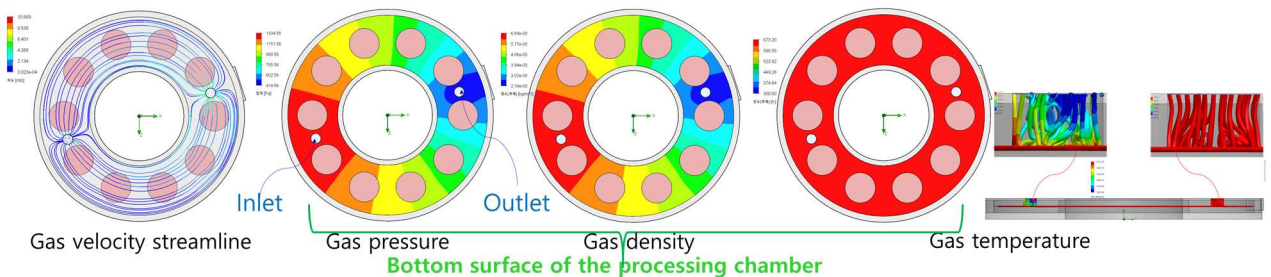


Fig. 1. Schematic diagram of the present ALD processing chamber and cluster tool for 300 mm wafers.



Gap=10 mm, Mass flowrate= 4.233×10^{-5} kg/s, Static pressure=1 Torr, Wafer temperature=400 °C, Inlet/outlet diameter=100 mm



Gap=1 mm, Mass flowrate= 4.233×10^{-6} kg/s, Static pressure=10 Torr, Wafer temperature=400 °C, Inlet/outlet diameter=100 mm

Fig. 2. Numerical results of the nitrogen gas flow fields for various operational conditions of the present ALD processing chamber.